Date of Notice

of Allowance : December 19, 2008

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

I hereby certify that this correspondence is being electronically filed with the United States Patent and Trademark Office on March 17, 2009 at or before 11:59 p.m. Profife Time under the Rules of 37 CFR §1.8.

: Kim, Nam Hun Confirmation No. 5813

Application No. : 10/593,857

Filed: September 22, 2006

Title : PLASMA CHAMBER HAVING PLASMA SOURCE COIL AND

METHOD FOR ETCHING THE WAFER USING THE SAME

Grp./Div. : 1792

Applicant

Examiner : Duy Vu Nguyen Deo

Docket No. : 58409/N305

COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Mail Stop Issue Fee Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Post Office Box 7068 Pasadena, CA 91109-7068 March 17, 2009

Commissioner:

Reasons for allowance are only warranted in instances in which "the record of the prosecution as a whole does not make clear his or her reasons for allowing a claim or claims." (37 CFR § 1.104(e))

Applicant believes the Examiner's stated reasons for allowance are unnecessary. The applicant does not necessarily agree with each statement in the reasons for allowance. While applicant agrees that the claims are allowable, applicant does not acquiesce with each statement in the reasons for allowance, that patentability requires each stated feature exactly as expressed by the Examiner, nor that each stated feature is required for patentability.

Appln No. 10/593,857 Stmt date March 17, 2009

Respectfully submitted,

CHRISTIE, PARKER & HALE, LLP

By Druguout
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